

<b>Notice of References Cited</b>	Application/Control No. 10/024,391	Applicant(s)/Patent Under Reexamination WATANABE ET AL.	
	Examiner Binh X Tran	Art Unit 1765	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,037,189	03-2000	Goto, Katsuhiko	438/31
	C	US-5,452,315	09-1995	Kimura et al.	372/46
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	M	US-			

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**NON-PATENT DOCUMENTS**

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	U	Sadao Adachi, "Chemical Etching of InGaAsP/InP DH Wafer", Journal of the Electrochemical Society, vol. 129, March 1982, pages 1053-1062.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.